

FIG. 1

FIG. 2

THICKNESS OF CHEMICAL OXIDE FILM ON SILICON WAFER SURFACE (nm)
TREATMENT TIME WITH OZONIZED WATER (sec)

FIG. 3

SC-1 CLEANING

OZONIZED WATER TREATMENT + HYDROFLUORIC ACID CLEANING

EXISTENCE RATIO OF Si ATOM COORDINATION NUMBER (%)

TIME PASSAGE SINCE CLEANING (hr)

FIG. 4

FIG. 5

HYDROGEN ANNEALING

OZONIZED WATER/HF CLEANING

SC-1 CLEANING

SPATIAL FREQUENCY ($/\mu\text{m}$)

FIG. 6

HYDROGEN ANNEALING

OZONIZED WATER CLEANING

EXTRAPURE WATER CLEANING

SPATIAL FREQUENCY ($/\mu\text{m}$)

Fig.1

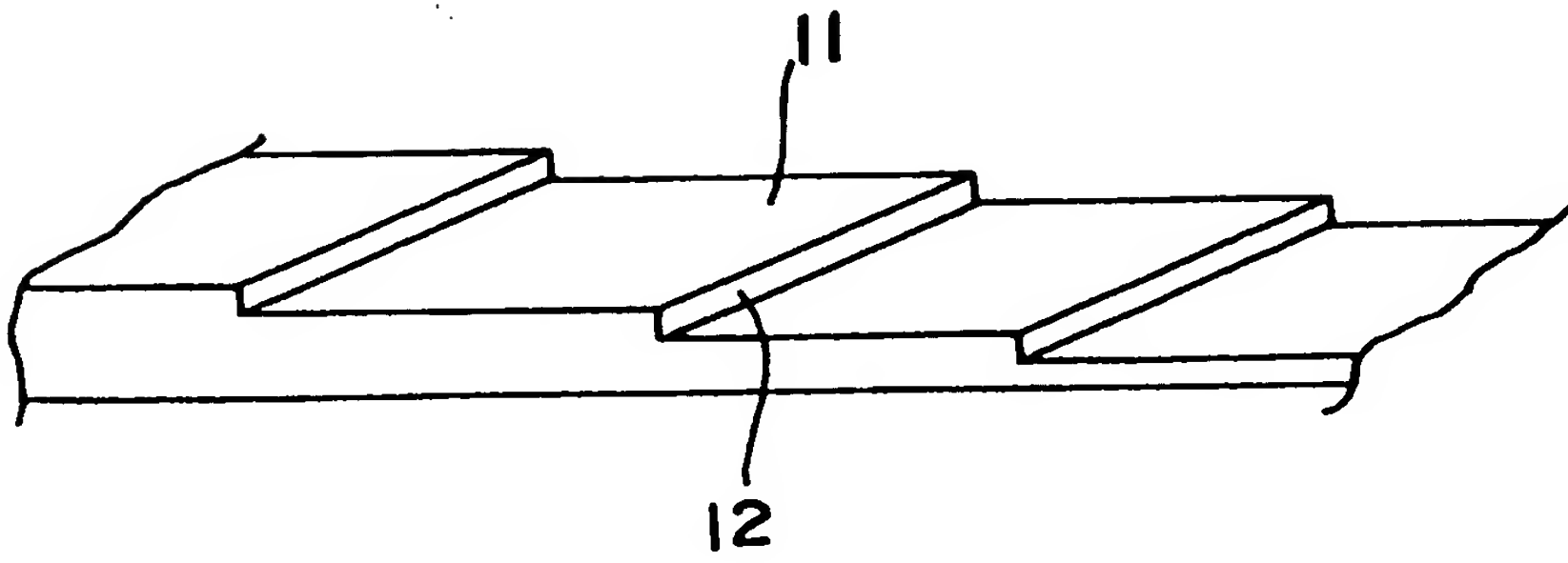


Fig. 2

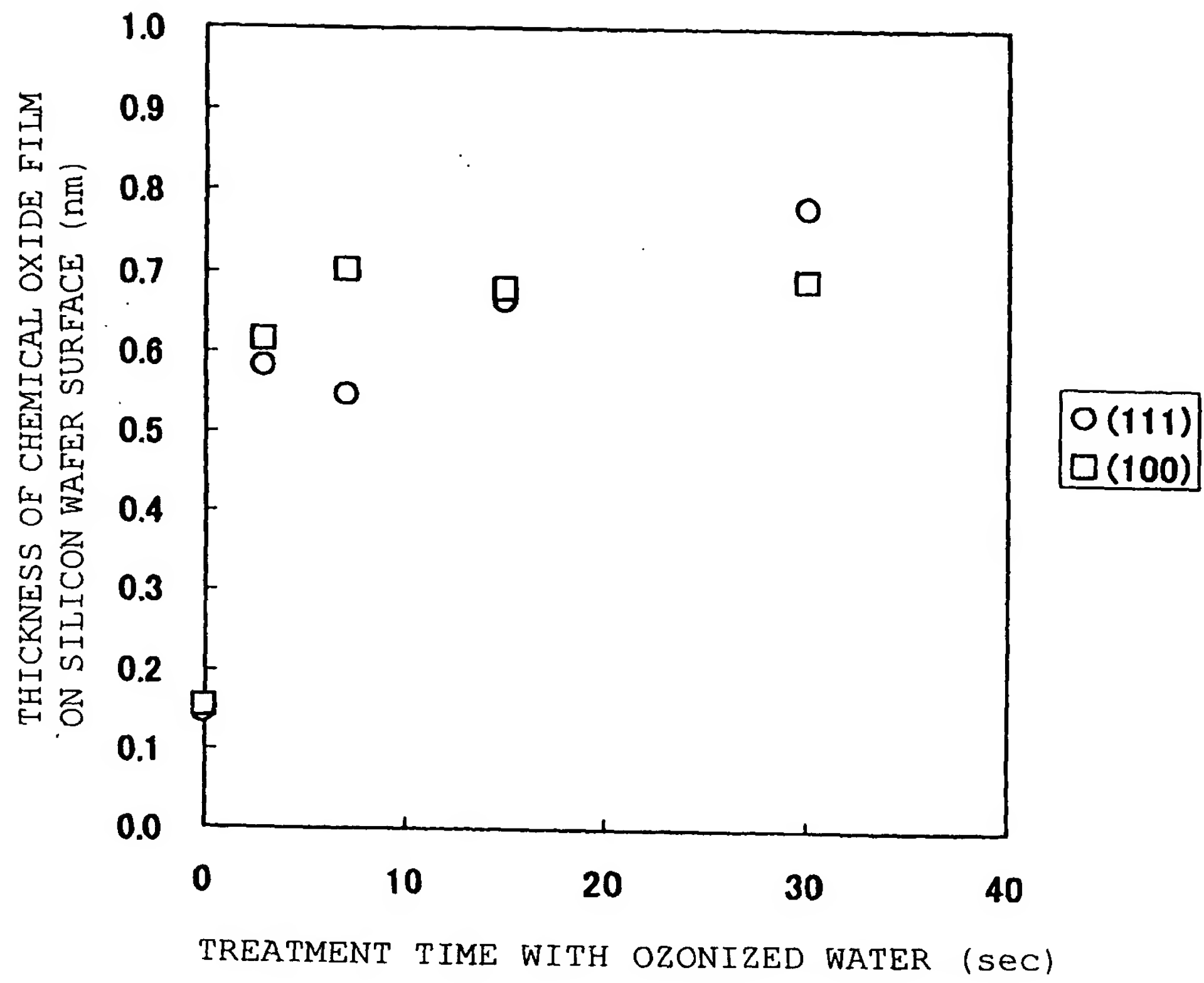


Fig. 3

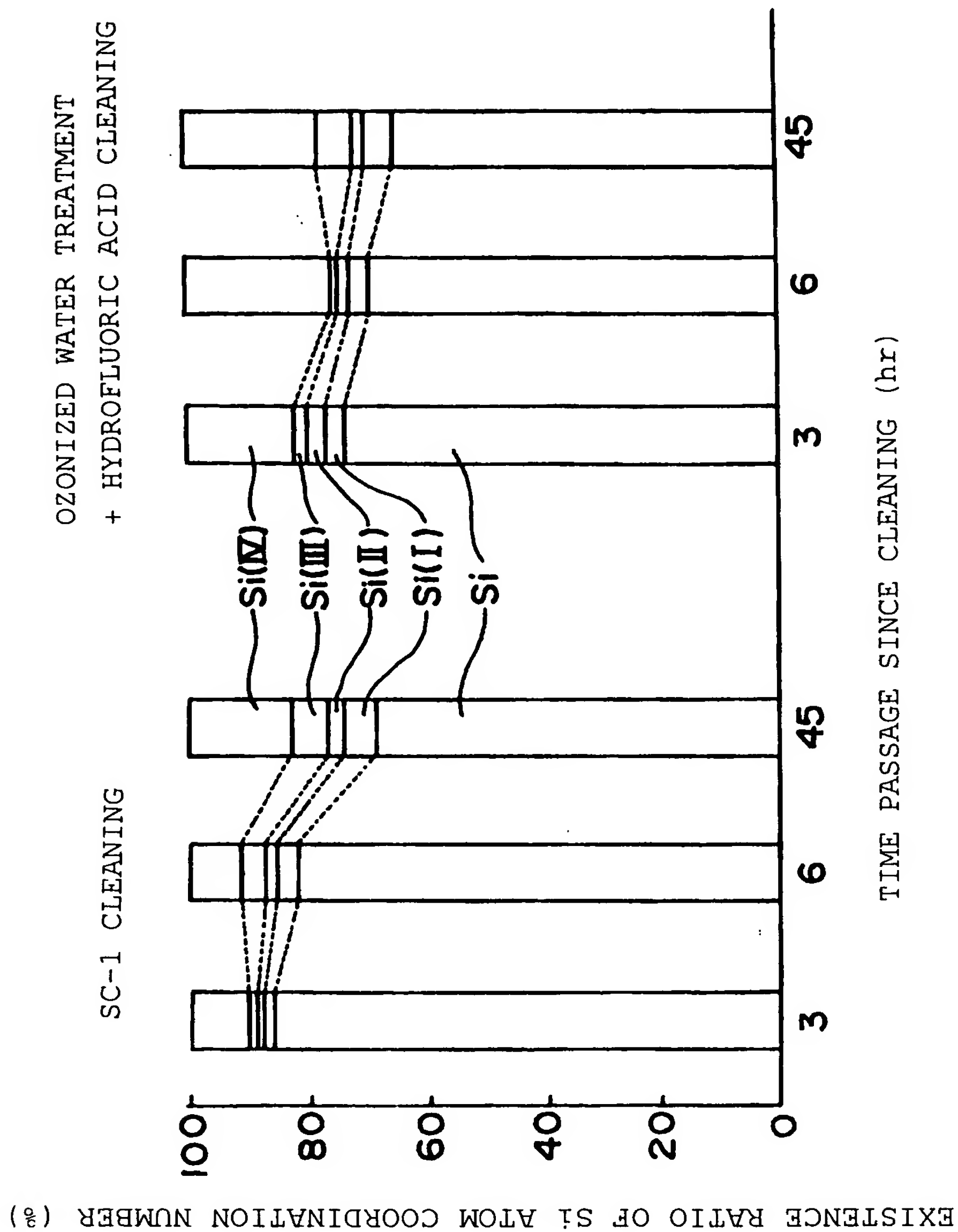


Fig. 4

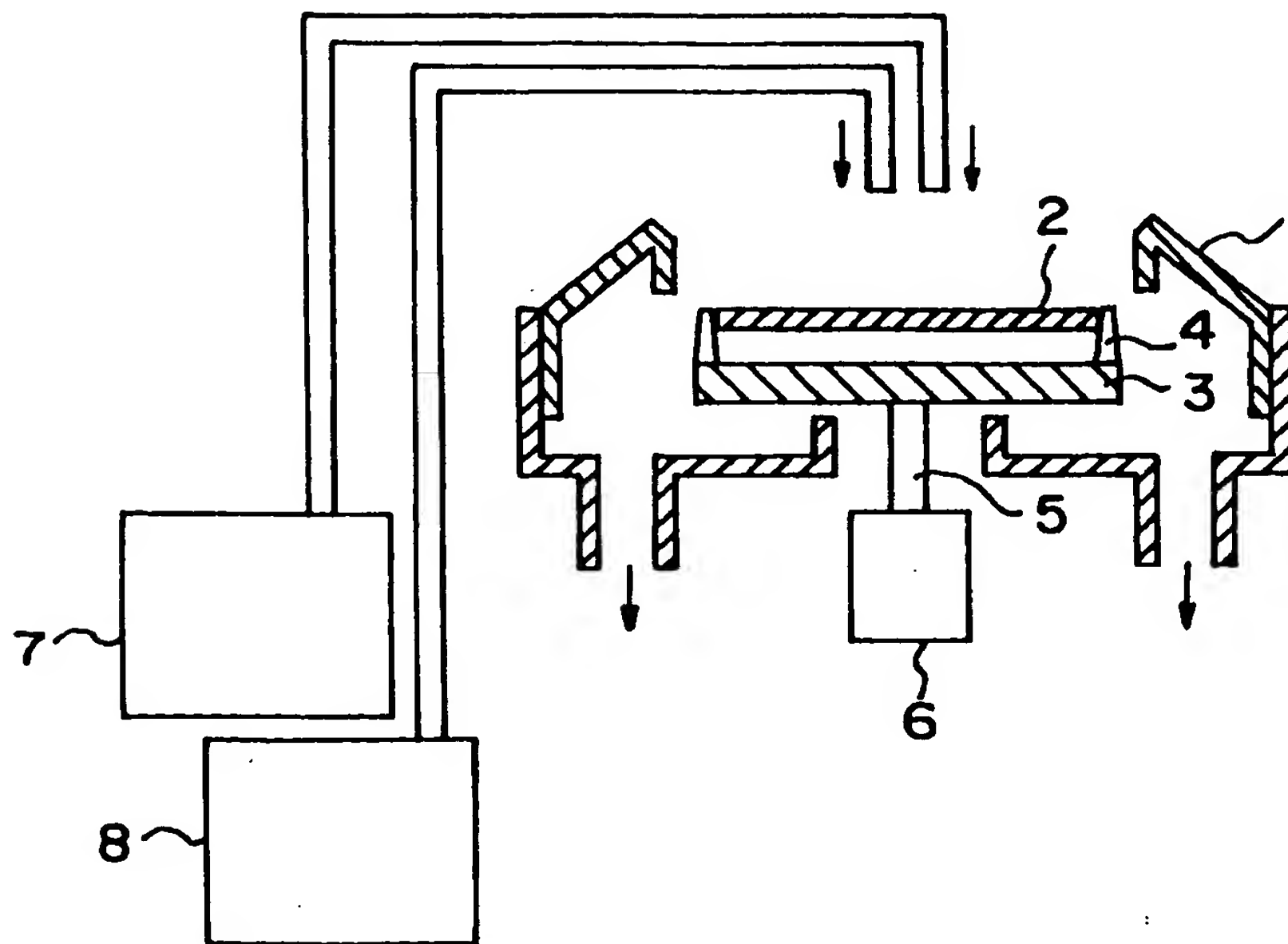


Fig. 5

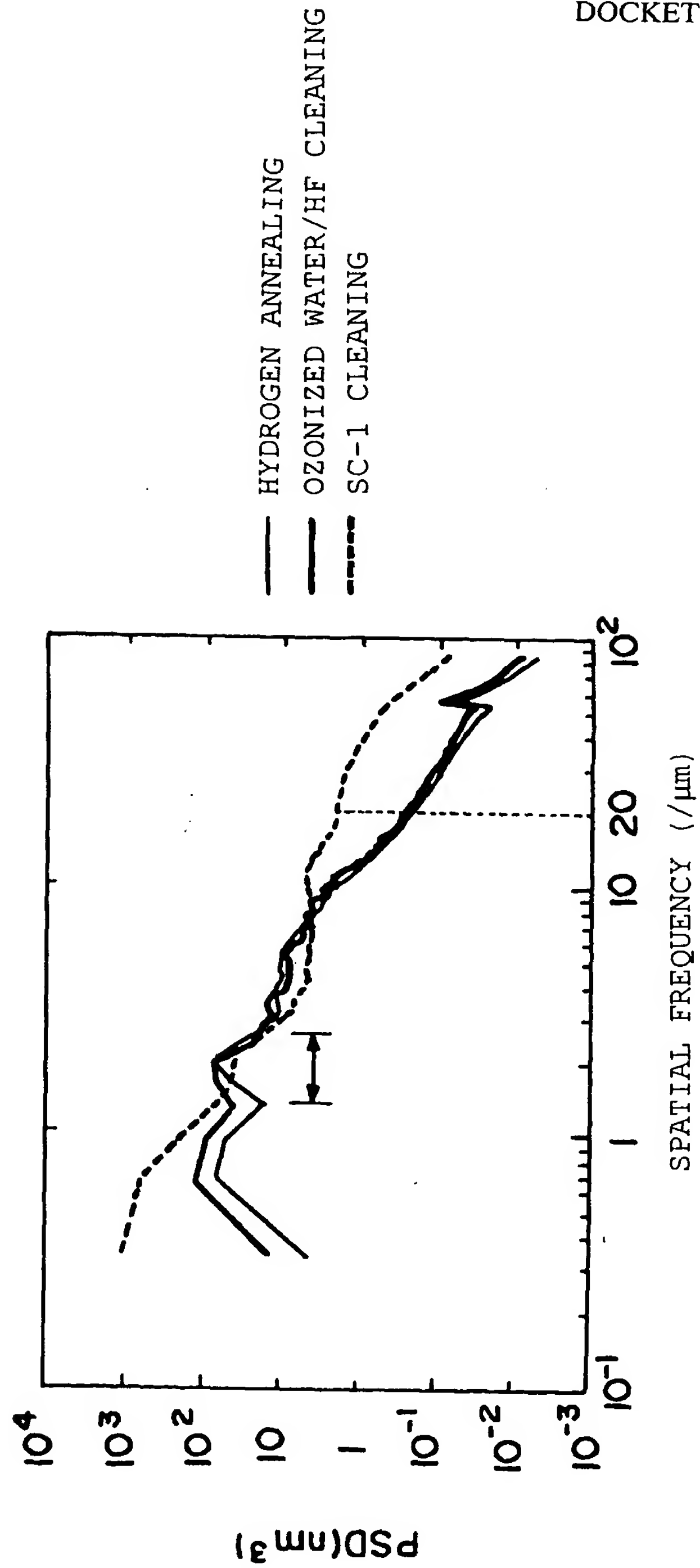


Fig. 6

